Device and Method for Coating of a Carrier Wafer

Abstract

A device for coating of an inner circular surface (7i) of a coating surface (3b) of a carrier wafer (3) with a coating material (9) with the following features:

- an application means (5) for applying a coating material (9) intended for coating of the inner circular surface (7i) to the inner circular surface (7i),
- a rotating means (2, 6) for accommodating and rotating the carrier wafer (3) around an axis (R) of rotation and for distribution of the coating material on the coating surface (3b),

characterized in that there are the second application means (4) for applying a coating inhibitor which at least inhibits the coating of the outer circular ring surface (7a) during the distribution of the coating material (9) to an outer circular ring surface (7a) which surrounds the inner circular surface (7i) and a corresponding method.

Figure 1